

1762

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of:  
Katsuhisa YUDA, et al.

Application No.: 09/818,972

Filed: March 27, 2001

For: METHOD OF FORMING SILICON OXIDE  
FILM AND FORMING APPARATUS  
THEREOF

Art Unit: 1762

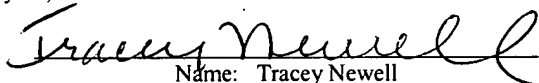
Examiner: Wesley D. Markham

Attorney Docket: GOM-02001

#7  
JUL 28 2003  
RECEIVED

**Certificate of Mailing**

I hereby certify that the foregoing documents are being deposited with the United States Postal Service as first class mail, in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on this date of July 22, 2003.

  
Name: Tracey Newell

**RESPONSE TO RESTRICTION REQUIREMENT**

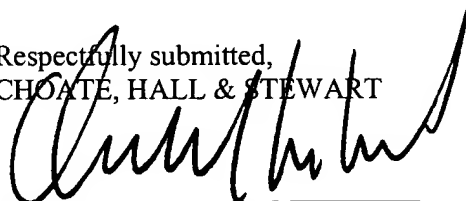
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated June 26, 2003, in which restriction was required, Applicant elects Group II, claims 7-12, drawn to an apparatus for forming a silicon oxide film on a substrate.

Favorable consideration and allowance are earnestly solicited. Should there be any questions after reviewing this paper, the Examiner is invited to contact the undersigned at 617-248-4038.

Respectfully submitted,  
CHOATE, HALL & STEWART



July 22, 2003  
Date

Donald W. Muirhead  
Reg. No. 33,978

Patent Group  
Choate, Hall & Stewart  
Exchange Place  
53 State Street  
Boston, MA 02109-2804  
Tel: (617) 248-5000  
Fax: (617) 248-4000